

Stress dependence of transport properties in sr - doped lanthanum titanate thin films

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ABSTRACT

In this study, Sr-doped LaTiO₃ (Sr_xLa_{1-x}TiO₃, SLTO, 0.16 < x < 0.86) thin films were grown on the LaTiO₃(100), SrTiO₃(100) and MgO(100) substrates by the off-axis rf magnetron co-sputtering system. In the experiment, we expect some La³⁺ ions were replaced by Sr²⁺ ions, and Sr_xLa_{1-x}TiO₃ thin films showed electrical conduction behavior. As the lattice match is different, Sr_xLa_{1-x}TiO₃ thin films are changed not only the stress between substrates and films, but also the electrical properties. The temperature dependence of resistivity and Hall effect were measured to study the transport properties, and we discussed the influence of lattice stress on Sr_xLa_{1-x}TiO₃ thin films.

Keywords : Sr_xLa_{1-x}TiO₃、lattice stress、Hall effect

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REFERENCES

- [1]S. Leoni, L. Craco, A. Ormeci, and H. Rosner, Solid State Sciences 8, 1138-1143 (2006) [2]Masatoshi Imada, Atsushi Fulimori, Yoshinori Tokura, Rev. Mod. Phys., Vol. 70, No. (2008) [3]C. C. Hays, J.-S. Zhou, J. T. Markert, and J. B. Goodenough, Phys. Rev. B 60, 10367 (1999) [4]B. Vilquin, T. Kanki, T. Yanagida, H. Tanaka, T. Kawai, Applied Surface Science 244, 494-497 (2005) [5]陳星宇, " 碓煙aTiO₃薄膜之磊晶成長與特性研究 ",大葉大學碩士論文,2007 [6]A.Ohtomo, D.A.M?荊ler, J. L. Grazul, and H. Y. Hwang, Appl. Phys. Lett. 80, 21 (2002) [7]Y. Okada, T. Arima, and Y. Tokura, Phys. Rev. B 48, 9677 (1993) [8]S. Liang, D.J. Wang, J.R. Sun, and B.G. Shen, Solid State Communication 148, 386-389 (2008) [9]J Li, F. B. Wang, P. Wang, M. J. Zhang, H. Y. Tian, and D. N. Zheng, Phys. Rev. B 75, 195109 (2007) [10]V. N. Bogomolov, E. K. Kudinov, and Y. A. Firsov, Sov. Phys. Solid State 9, 2502 (1968) [11]B. Vilquin, T. Kanki, T. Yanagida, H. Tanaka, T. Kawai, Solid State Communication 136, 328-332 (2005) [12]Hiroaki Muta, Ken Kurosaki, and Shinsuke Yamanaka, Journal of Alloys and Compounds 350, 292-295 (2003) [13]Y. Tokura, Y. Taguchi, Y. Okada, Y. Fujishima, and T. Arima, Phys. Lett. 70, 2126 (1992) [14]美國國家標準和技術院(National Institute for Standards and Technology, NIST) [15]李志晃, " 摻鐳SrTiO₃之傳輸特性研究 ",大葉大學碩士論文,2006 [16]S. Gariglio, J. W. Seo, J. M. Triscone, Phys. Rev. B 63, 161103 (2001) [17]J. R. Sun, H. W. Yeung, H. K. Wong, T. Zhu, B. G. Shen, Eur. Phys. J. B 35, 481 (2003) [18]David Olaya, Feng Pan, Charles T. Rogers, and John C. Price, Appl. Phys. Lett. 80, 16 (2002) [19]T. Mihara, K. Shibuya, T. Ohnishi, H. Koinuma, and M. Lippmaa, Thin Solid Films 486, 63-66 (2005) [20]S. Hashimoto, L. Kindermann, F. W. Poulsen, and M. Mogensen, Journal of Alloys and Compounds 397, 245-249 (2005) [21]M. Cwik, T. Lorenz, J. Baier, R. M?荊ler, G. Andr?? F. Bour?縹, F. Lichtenberg, A. Freimuth, R. Schmitz, E. M?荊ler-Hartmann, and M. Braden, Phys. Rev. B 68, 060401 (2003) [22]S.Y. Jang, N. Nakagawa, S.J. Moon, T. Susaki, K.W. Kim,

Y.S. Lee, H.Y. Hwang, and K. Myung-Whun, *Solid State Communications* 149, 1760-1764 (2009) [23] Y. Fujishima, Y. Tokura, and T. Arima
Phys. Rev. B 46, 17 (1992)